

Notice of References Cited	Application/Control No. 10/665,275	Applicant(s)/Patent Under Reexamination WAGO, KOICHI	
	Examiner Martin J. Angebrannt	Art Unit 1756	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Savas et al. 'Large area achromatic interferometric lithography ...' J. Vac. Sci., Technol. B., Vol. 14(6) pp. 4167-4170 (11/12-1996)
	V	Savas et al., 'Achromatic interferometric lithography for 100 nm period gratings and grids", J. Vac. Sci., Technol. B., Vol. 13(6) pp. 2732-2735 (11/12-1995)
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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